

ESSDERC 2013

Emerging Memories

Livio Baldi, Gurtej Sandhu

Micron Technology



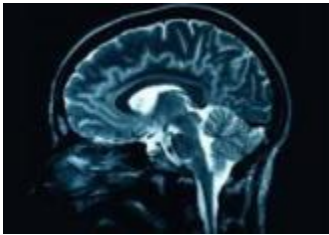
Outline

- ❑ Solid State Memories: a success story
- ❑ A lot of alternatives:
 - Prototypal memories
 - New concepts
- ❑ From cell to memory
- ❑ Is there a winner?

Outline

- ❑ Solid State Memories: a success story
- ❑ A lot of alternatives:
 - Prototypical memories
 - New concepts
- ❑ From cell to memory
- ❑ Is there a winner?

There is more than one memory



In our head

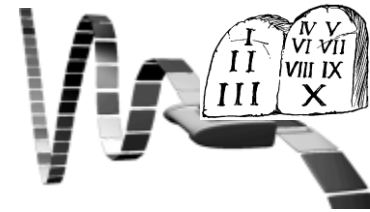
Retention time:

- **Short term memory:** what was in previous slide? (if you still remember it)
- **Long term memory:** what did you learn at school?

But also functions:

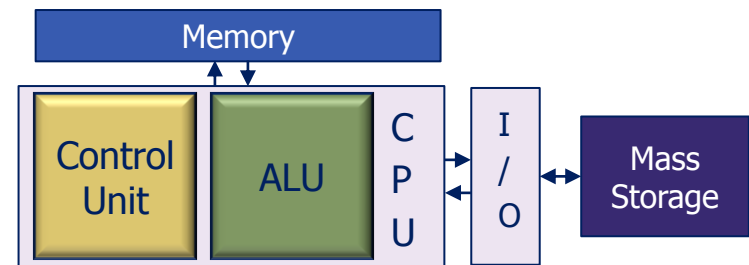
- **Procedural memory:** how to ride a bike, make a knot in your tie, ..
- **Semantic memory:** remembering well defined data, e.g. a phone number
- **Episodic memory:** past events, e.g. your trip here, your holidays, the plot of a movie.

and in computers



In Turing machine:

- A memory for **data** (endless tape)
- A memory for the **instructions**



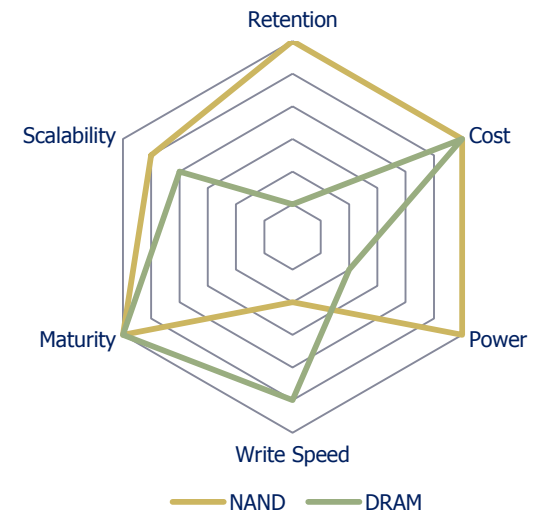
Von Neumann architecture:

- One main memory for data and program
- One mass storage unit

Memory performances

There is no single parameter to characterize memories:

- Size: how many bits in a single device?
 - Retention: how long is information conserved without power supply?
 - Endurance: how many times can I change the content before degradation?
 - Programming speed: how fast can I change the content?
 - Access speed
 - Latency: how long before the first data out?
 - Throughput: which is maximum reading data flow?
 - Power
 - Programming
 - Reading
 - Stand-by
 - COST: how many bucks per bit (or Byte, or Gigabyte)?
- And others (BER, T range,)



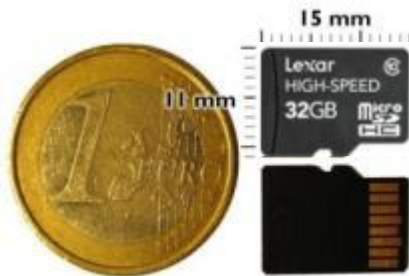
The evolution of memory systems

- ▶ Early Computing
- ▶ Early Storage

IBM Hard Disk Drive 1965
Weight > 1ton
Capacity: 5Mbyte

Today:

- 32Gbyte microSD

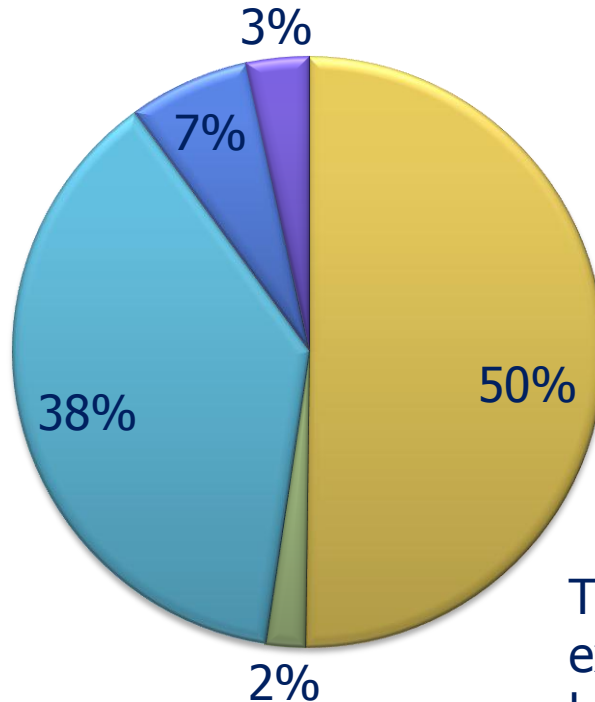


Memory market

Sales 2012

Total market: 52 B US\$

■ DRAM ■ SRAM ■ NAND ■ NOR ■ Others



Volatile memory: 52%
Non-volatile: 48%

The market is dominated by two extreme types of memory, with the lowest costs.

Source: IHS iSupply

Scaling Issues

NAND

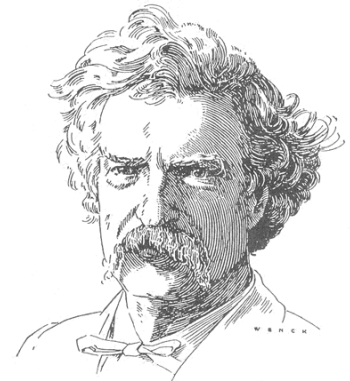
- ▶ Active dielectric thickness
- ▶ Isolation aspect-ratio and parasitic coupling
- ▶ Statistical effects increase due to few electrons storage
- ▶ Increasing weight of Error Correction Algorithms

• DRAM

- ▶ Cell transistor architecture in a 4F2 size (refresh time)
- ▶ Cell capacitor material with high-k dielectric
- ▶ Cell capacitor aspect ratio

BUT:

“The reports of my death are greatly exaggerated”.



3-D memories



Manhattan approach:

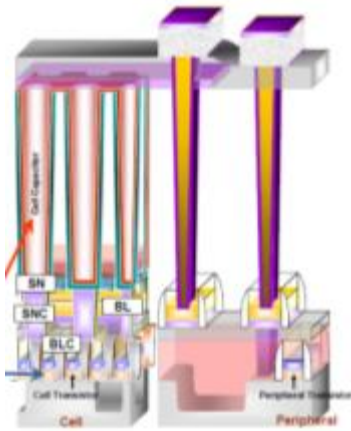
- more efficient use of real estate by stacking memory cells.

East block approach

- More efficient use of space by putting more bits in the same cell.

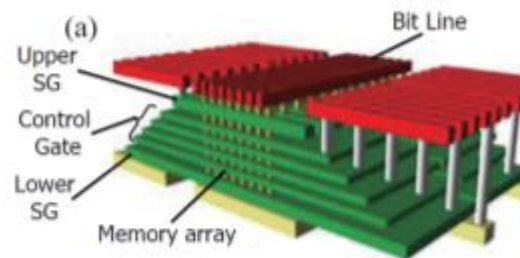
DRAM memory

- From planar capacitor to
- vertically stacked capacitor
- vertical transistor as next step

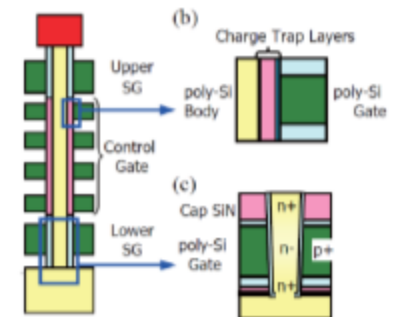


NAND memory

- Vertically stacked memory cells
- Polysilicon channel
- Better use of area, but
- Cell footprint cannot be scaled
- Density = number of layers
- Cost = number of layers
- Multibit/cell



BiCS

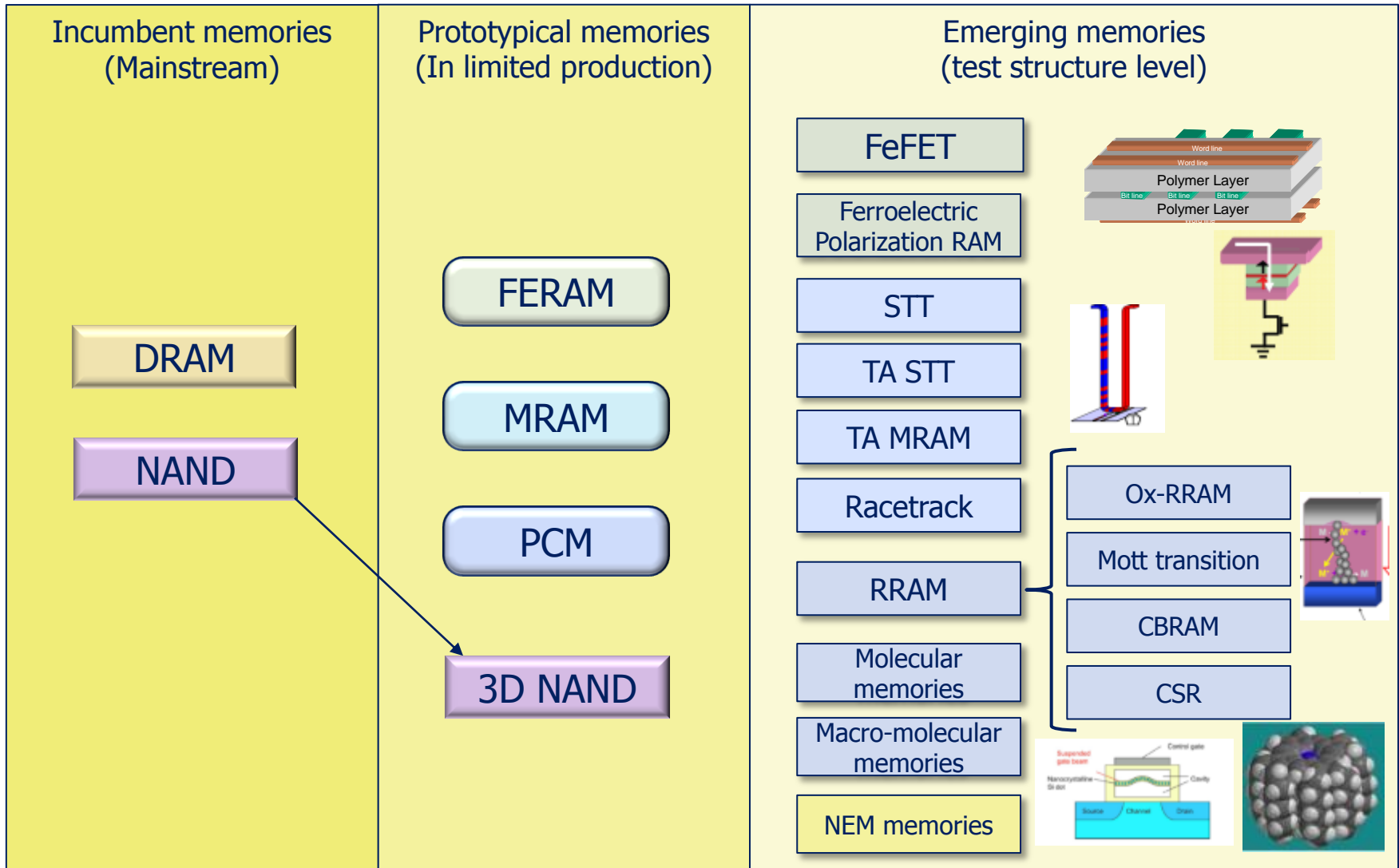


*VLSI 2007

Outline

- ❑ Solid State Memories: a success story
- ❑ A lot of alternatives:
 - Prototypal memories
 - New concepts
- ❑ From cell to memory
- ❑ Is there a winner?

Memory cell landscape



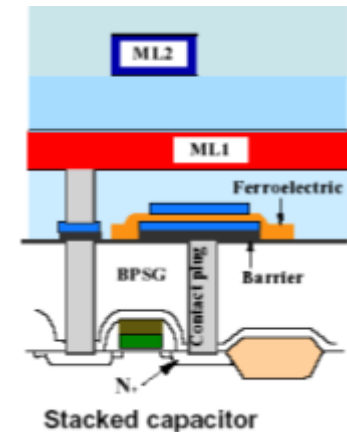
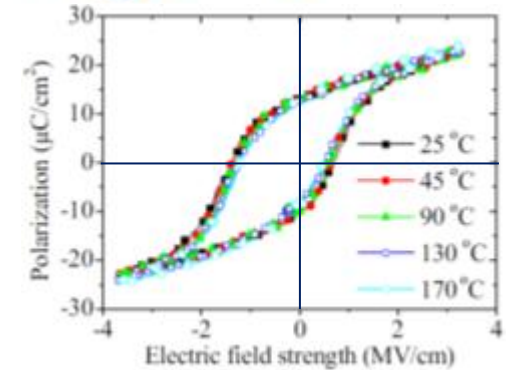
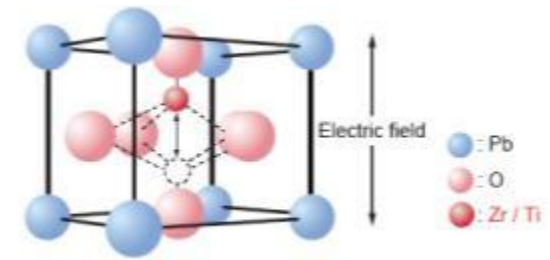
Outline

- ❑ Solid State Memories: a success story
- ❑ A lot of alternatives:
 - Prototypal memories
 - New concepts
- ❑ From cell to memory
- ❑ Is there a winner?

Ferroelectric Memories

▶ Storing mechanism

- Permanent polarization of a ferroelectric material induced by external electric field, related to ion displacement in the crystal cell.
- Most common ferroelectric device is the FeRam
- DRAM-like cell: 1 transistor, 1 capacitor (1T/1C)
- Sensing through the displacement current associated to the polarization switch (destructive reading)
- Two base materials used
 - PZT ($\text{Pb}_x\text{Zr}_{1-x}\text{TiO}_3$), known since long time
 - SBT ($\text{SrBi}_2\text{Ta}_2\text{O}_9$), more recent material (easier thickness and voltage scalability)



FERAM: Advantages and Issues

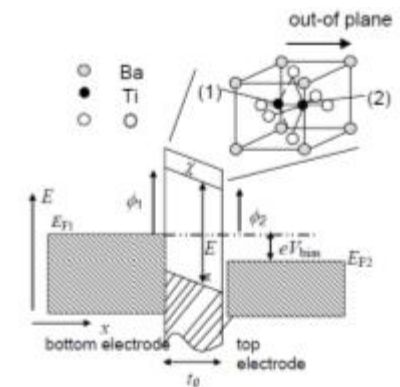
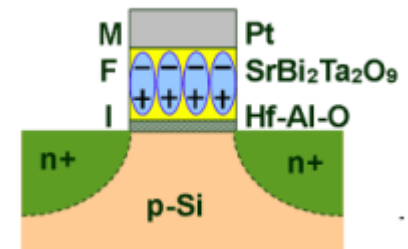
- ▶ Advantages:
 - Fast (<100ns) and low energy write.
 - High write endurance.
 - Medium/low voltage write.
- ▶ Issues:
 - Difficult process integration.
 - Large cell size (25 F²) and limited scaling potential with respect to Flash and DRAM.
 - Limited read endurance, destructive read-out.
 - Technology gap vs. established technologies.
- ▶ Commercially available up to 8Mb (Ramtron, Fujitsu)
- ▶ Interest revamped by two emerging concepts

FeRAM emerging Memories

► Different sensing mechanism

- Ferroelectric FET: integration of ferroelectric material in transistor gate; Flash-like cell: 1 transistor.
- Direct sensing of cell threshold, non destructive reading.
- Issues: large k of ferroelectric material \rightarrow thick ferroelectric layer \rightarrow max. aspect ratio limits cell size
- Read disturbs
- One paper at this conference

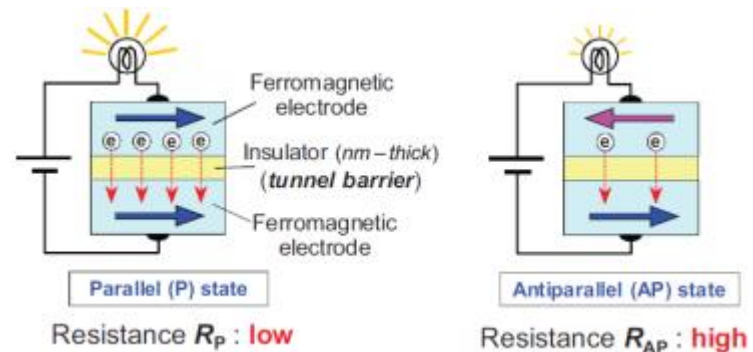
- Ferroelectric Polarization RRAM: M-I-M tunnel diode where the dielectric is a ferroelectric material
- Changing ferroelectric polarization can modify the charge injection/transport properties of FE
- Different mechanisms claimed: Schottky barrier, lattice strain,...
- Low reading current due to tunnel effect.



Magnetic Memories

- ▶ Storing mechanism
 - Permanent magnetization of a ferromagnetic material
- ▶ Sensing mechanism
 - Tunnelling current between two ferromagnetic layers
 - One 'free' magnetic layer (easily switchable) and one pinned reference layer
 - Tunnel current depending on mutual orientation of magnetic layers

- ▶ Main advantages
 - Fast write (<100ns)
 - Low voltage write
 - High write endurance

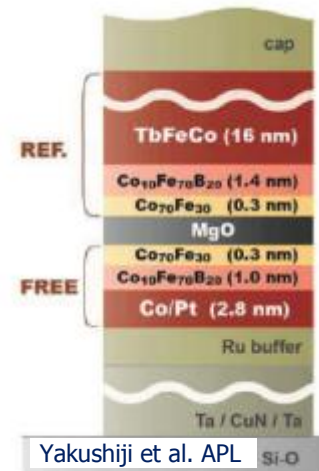
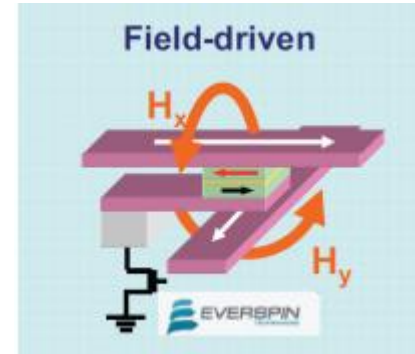


- ▶ Freescale first product: 4Mb in 2006



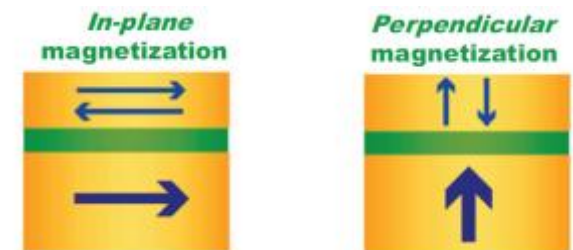
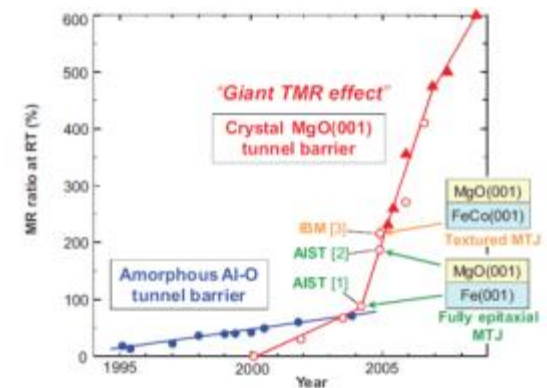
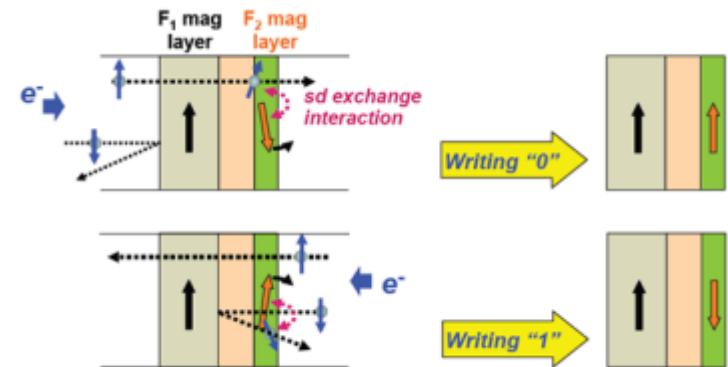
First Generation

- ▶ Tunnel MagnetoResistance (TMR)
 - Programming by current induced magnetic field
- ▶ Main issues
 - Difficult process integration (10-12 layers required due to layer matching requirements)
 - Large cell size vs Flash and DRAM (40-80 F²: IBM, Toshiba), difficult scaling
 - Large write current (>10mA/byte), small read signal
 - Programming disturbs by stray magnetic field
- ▶ Heating can assist the switching of the 'free' layer in programming and keep retention and disturb immunity low (Thermally assisted MRAM)
- ▶ However heat propagation can become an issue to scaling



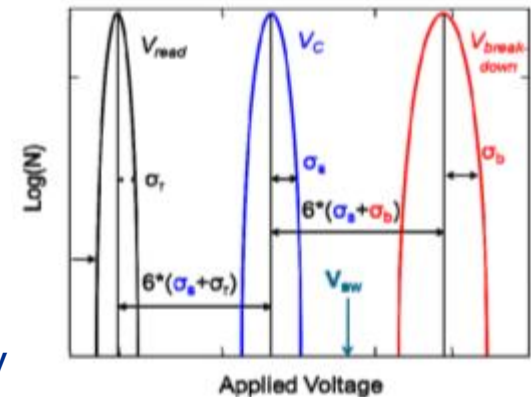
Second Generation

- ▶ Spin-Transfer Torque programming
 - Memory switching by injection of spin-polarized electrons
 - All current directly used for switching
 - Current scales with area.
 - Less disturbs
- ▶ MgO dielectric replacing AlO₂ -> much better signal
- ▶ Perpendicular magnetization instead of parallel -> better scaling, better thermal immunity.
- ▶ Cell size down to 14 F2 reported in literature, but average is more than 20.



Some concerns....

- ▶ Reading margins
 - 200% is considered high for MRAM, but very low for other NVM types
- ▶ Operating margins:
 - Writing voltages in the 0.5-0.6V range;
 - TDDB of dielectric is around 1-1.5V;
 - Read voltage in the 0.15-.2V range
 - Very low margins for safe operation and disturb immunity
- ▶ Tight process control needed due to multilayer structure.
- ▶ Possibility of multi-bit operation proposed, but low reading margins.
- ▶ Complex read schemes:
 - Conventional with dummy cell, but heavy stress on technology control
 - Self-reference but requires write back



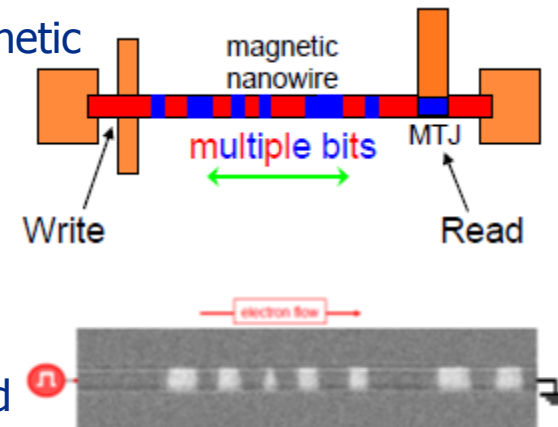
J.M.Slaughter, et al. IEDM 2012

TDDB: Time Dependent Dielectric Breakdown

MRAM emerging memories

▶ Race track memories

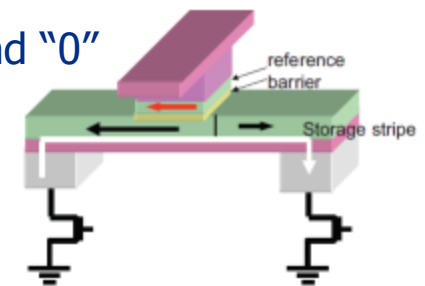
- Proposed by IBM (S.Parkin et al., Science 320, 190, 2008)
- Shift register organization: bit as domain orientation in magnetic nanowire.
- One write head and one read head at the ends of the strip.
- Main issues:
 - Control of domain motion.
 - Current values for domain shift
 - Power consumption: reading requires domain shift and rewriting



S.Parkin et al. IEDM 2011

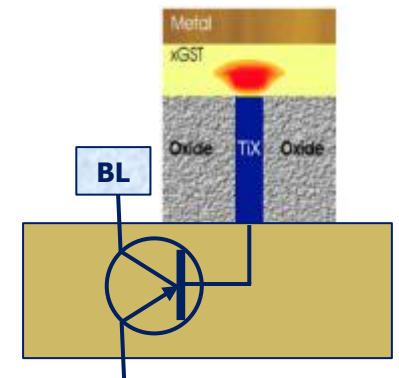
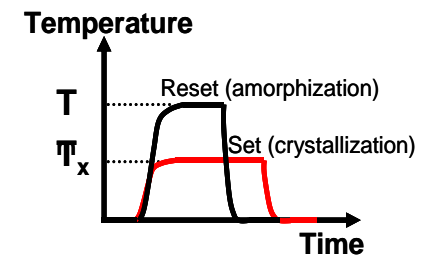
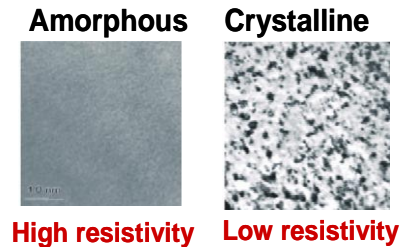
▶ Alternative Domain Wall

- Originally proposed by NEC (H.Numata et al. VLSI 2007)
- Domain wall is shifted left and right by a current, to give "1" and "0"
- Reading by tunneling current in spin diode.
- Less reliability problems, but large cell.

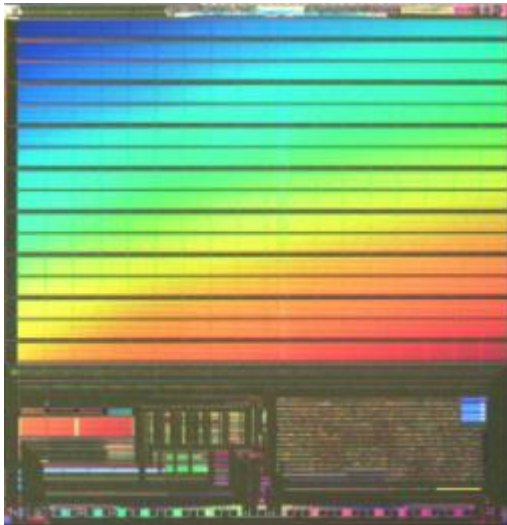
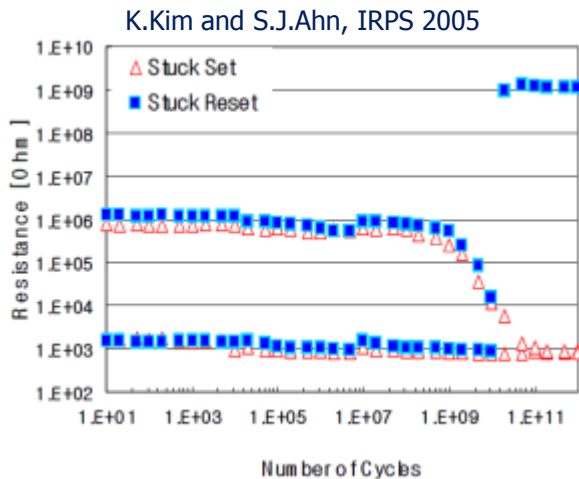


Phase Change Memories

- ▶ Storing mechanism
 - Polycrystalline to amorphous transition in chalcogenide.
- ▶ Writing mechanism
 - Current pulse to melt material followed by fast or slow cooling.
- ▶ Sensing mechanism
 - Resistivity measurement at low currents
- ▶ Cell structure
 - 1 transistor, 1 resistor (1T/1R)
 - Two options: MOS transistor for embedded; bipolar for high density
- ▶ Basic material:
 - GST ($\text{Ge}_2\text{Sb}_2\text{Te}_5$ is the most usual, but other compositions also possible)



PCM: Advantages and Issues

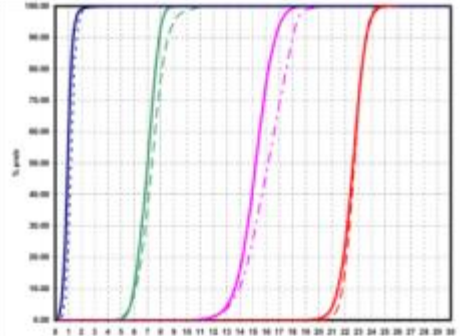


- ▶ Main advantages
 - Fast write (<100 ns)
 - Good read signal window (factor ten in resistance)
 - Medium/low voltage write
 - Bit granularity
 - High endurance
 - Cell size comparable to Flash and DRAM
 - Good scalability
- ▶ Main issues
 - Process integration for GST
 - Heater-GST interface optimization
 - Writing current (~ 1 mA), scalable with cell size
 - Retention at high temperature (150° C). Common issue to all emerging memories
- ▶ 1Gbit memory available in 45nm technology
 - DDR2 interface
 - NOR Flash legacy spec + bit alterability
 - Chip area: 37.5mm^2
 - Power supply range: $1.7\text{V} \div 2.0\text{V}$
 - Temperature Range: $-40\text{C} \div +85\text{C}$

PCM emerging memories

▶ Multi-level storage

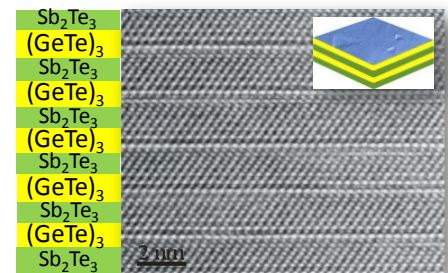
- Proposed by IBM (Papandreou N. et al., IMW 2011)
- Using the large Ion/Ioff ratio of PCM cell it seems possible to store 2-3 bit/cell.
- Densities comparable with NAND appear possible.
- Main issues: disturbs, threshold drifts



Courtesy of CAMELS project, partially funded under FP6 Programme

▶ Super-Lattice Memory

- Originally proposed by NEC (Chong et al. Appl. Phys. Lett. 88 (2006))
- A super-lattice of chalcogenide layers with thickness within the phase-transition limits.
- Phase transition assumed to be by motion of Ge atoms without melting.
- Faster switching, much lower current.
- Exact mechanism and limits not yet clarified.



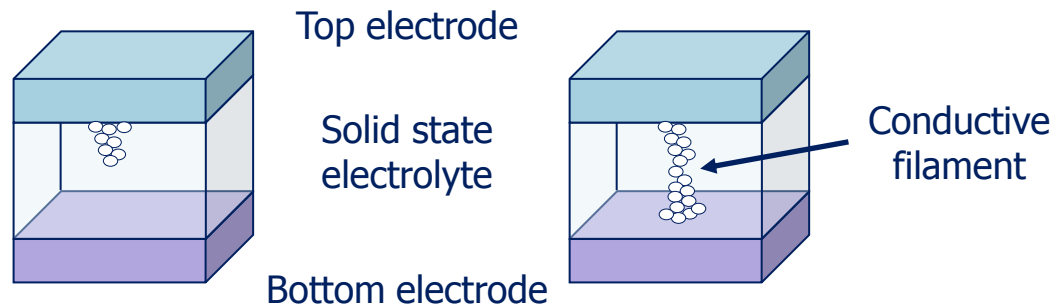
Courtesy of PSTRY project, partially funded under FP7 Programme

Outline

- ❑ Solid State Memories: a success story
- ❑ A lot of alternatives:
 - Prototypal memories
 - New concepts
- ❑ From cell to memory
- ❑ Is there a winner?

Resistive memories

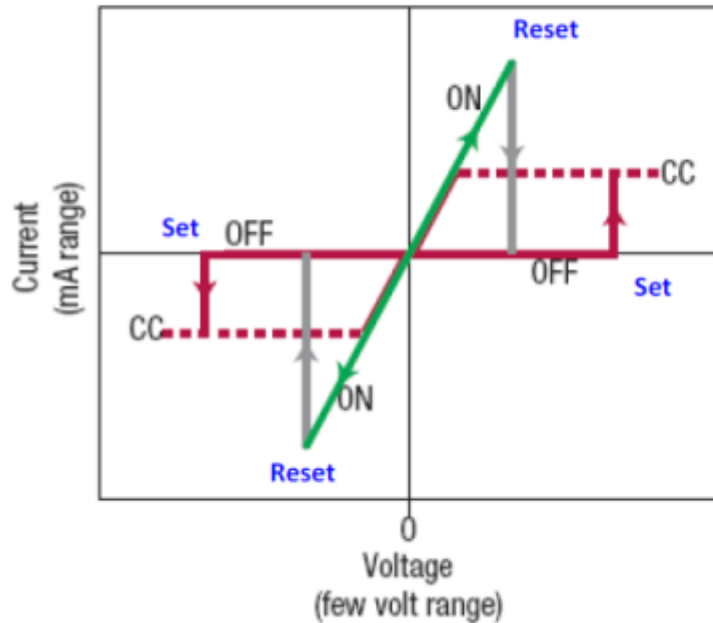
- ▶ Formation (and dissolution) of a conductive path between two electrodes:
 - Induced by a voltage pulse
 - Reversible
 - Persistent in time (non volatility)
 - Such as to induce large changes in resistance



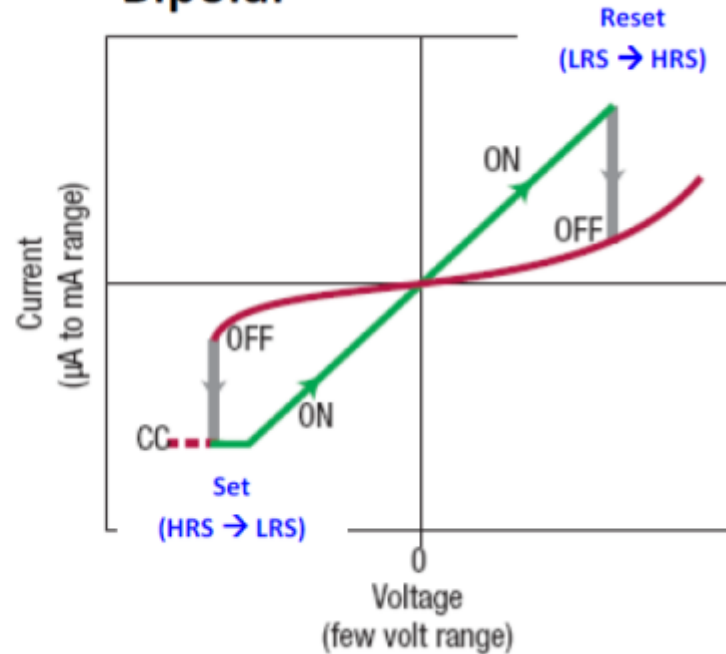
- ▶ Conductive filament can have different natures:
 - Metal ions (conductive bridge RRAM or CBRAM)
 - Formation of traps (Oxygen vacancies) OxRRAM
- ▶ Generally requires an initialization process ('forming')
- ▶ Exact mechanism not yet defined, but phenomenological models available.
- ▶ Electrode material plays a critical role.
- ▶ 6 out of 8 papers on memories at this conference

Switching polarity

Unipolar



Bipolar



Type a – Unipolar switching device:

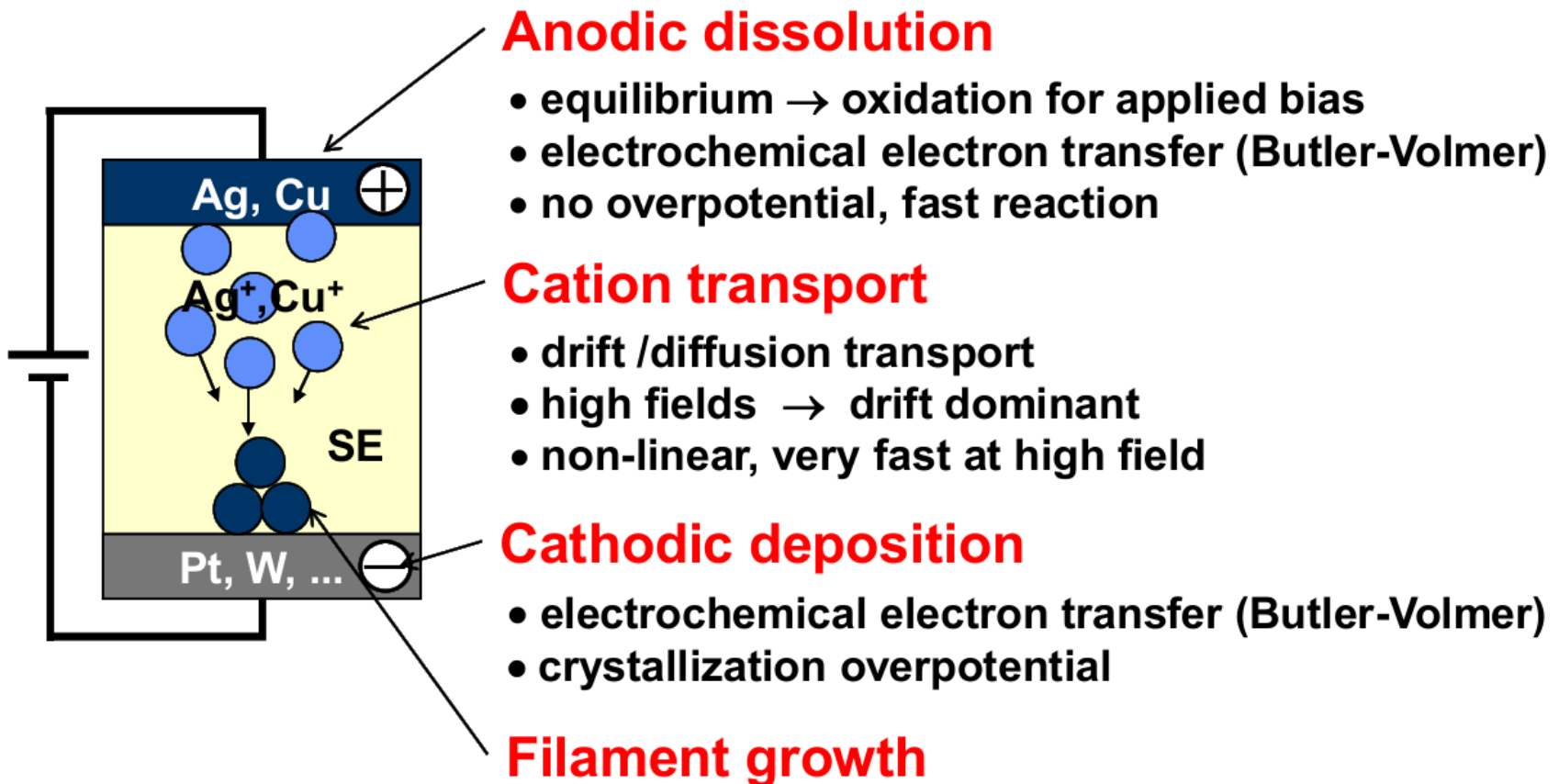
- Switching between ON&OFF depends only upon E amplitude
- Breakdown-type mechanism for Off to On transition (SET)

Type b – Bipolar switching device:

- Switching between ON&OFF depends upon E polarity
- Less stress on material

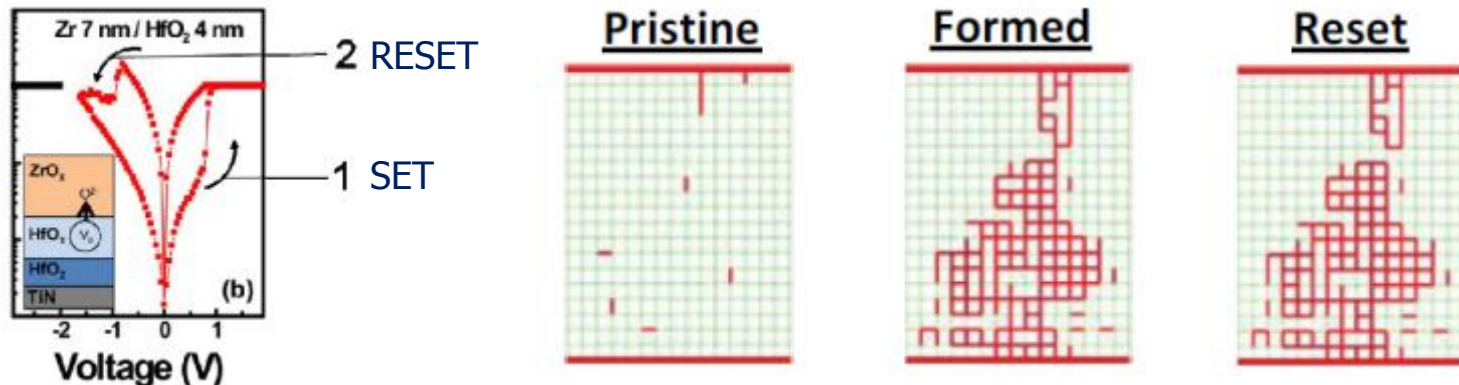
Conductive Bridge RAM

Reaction environment



Oxide bridge RAM

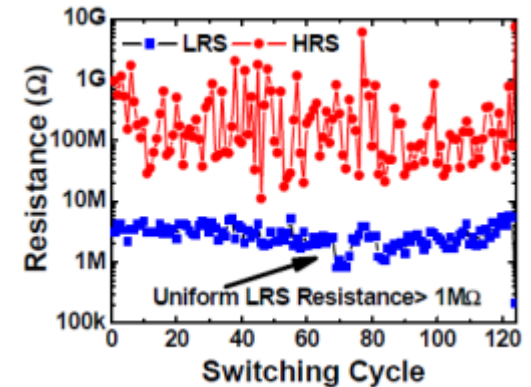
- ▶ Trap-assisted conduction in metal oxide
 - Formation of a vacancy filament through a forming process (soft breakdown)
 - Conduction through electron tunneling via Oxygen vacancies
 - RESET by dissolution of the filament by oxygen migration and recombination.
 - SET by regeneration of filament through opposite voltage.



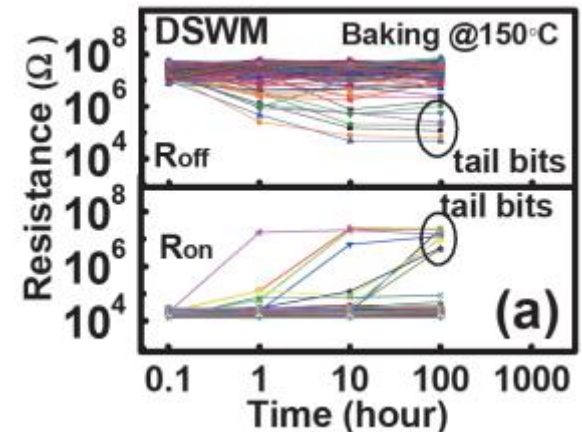
- ▶ “Soft breakdown” not very reproducible:
 - Dissolution of filament not always complete. High Ioff currents in RESET.
 - Large variability in On and especially Off states
 - Heating can play an important role

Main concerns of RRAM

- ▶ Filament formation not very reproducible
 - Strong dependence on forming process conditions
 - Strong variation in Ioff current, both cell to cell and with cycling
 - RTN noise in high resistance status
 - Sensitive to temperature and voltage stress.
- But:
 - Forming seems avoidable for scaled cells
 - More sophisticated cell architecture and programming algorithms emerging
 - Window seems to improve with cycling
- ▶ Not clear understanding of mechanism:
- ▶ Complex interplay of cell and electrode materials
- ▶ Large variety in materials investigated; materials with an history of integration in CMOS technology (TiO, WO, HfO, TaO) are preferred



Hong-Yu Chen et al., IEDM 2012

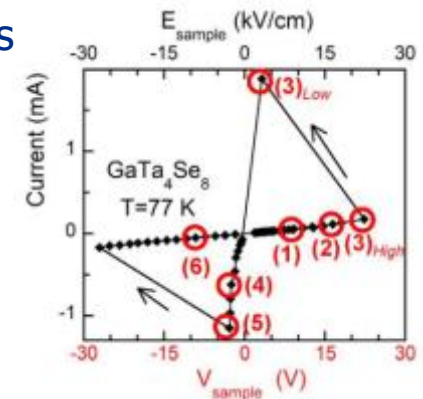


Y.L.Song et al., VLSI 2013

Other possible RRAM mechanisms

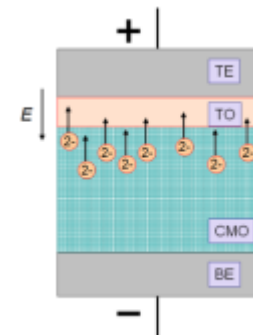
► Mott transition RAM (CeRAM)

- Charge injection induces a transition from strongly correlated to weakly correlated electrons, resulting in an insulator-metal transition.
- Explored in VO₂, SmNiO₃, NiO or more complex combinations (L.Cario et al., Advanced Materials 2010)
- Exact mechanism still not clear (crystal deformation?)
- Non volatile?
- Needs high voltages; 25% Ron/Roff margin at room T^o



► Mixed Valence Oxide RAM

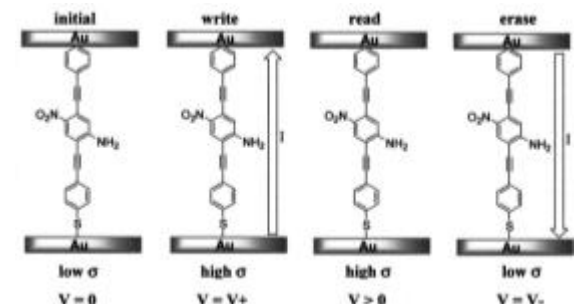
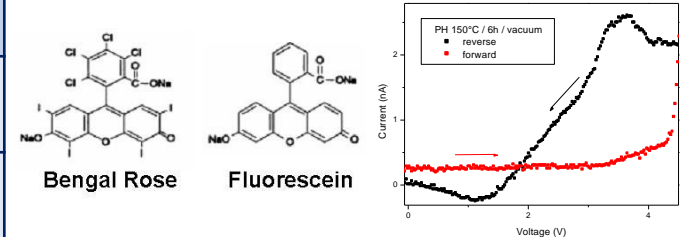
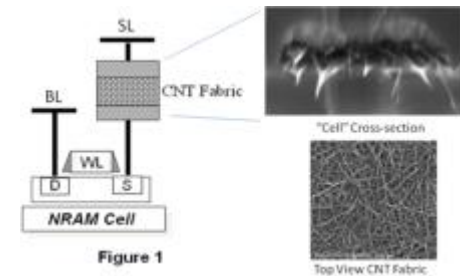
- Change of tunnel barrier height due to Oxygen ions exchange with conductive metal oxide (R.Meyer et al. NVMTS 2008)
- Bipolar switching. One order of magnitude between Ron/Roff.
- A 64Mbit memory presented at ISSCC 2010.



More NVM Concepts: Longer Term

A not exhaustive list.....

Nano-electromechanical memory (NEMM)	
Bi-stable nano-electromechanical switch	Electrostatic Attraction + Van der Waals Adhesion e.g. Nantero CNT memory, cantilever devices
Issues: scalability, endurance, sticking.	
Macromolecular (polymeric) memory	
Polymers with two resistivity states (bengal rose, fluoreiscline)	Switching between different redox states, charge trapping
Issues: material stability, mechanism not yet clear	
Molecular memories	
Single molecules in a cross-point array	Voltage Driven Change in electronic states in Redox
Issues: difficulty in handling single molecules, sensitivity to several parameters, addressing problems.	



Outline

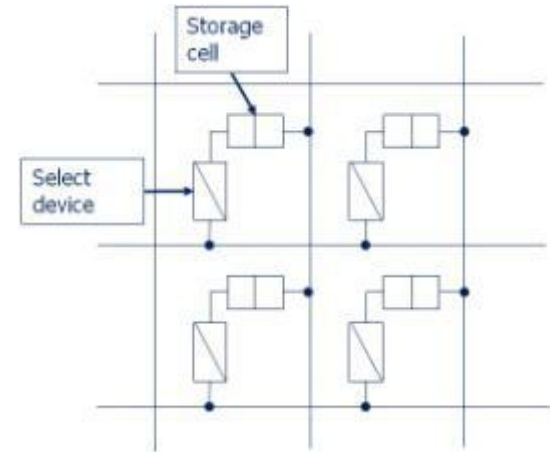
- ❑ Solid State Memories: a success story
- ❑ A lot of alternatives:
 - Prototypal memories
 - New concepts
- ❑ From cell to memory
- ❑ Is there a winner?

Memory as a system

- ▶ Two main functions to an electronic memory:
 - Data storage
 - Data retrieval
- ▶ Memories are organized in arrays
 - Storing and retrieval requires selecting the cell
 - Cell selection can be the major issue for different types of storage and is the main contributor to size of memory array.
- ▶ Cell selection is often the most critical issue for emerging memories.

Cell selector and array organization

- ▶ Cell selection within the array, and array characteristics can play a major role in the selection of memory technology.
- ▶ The selector allows a given memory cell in an array to be addressed for read or write.
- ▶ Key requirements for select device:
 - Strong non linear characteristic (switch).
 - In the On state: capability to handle the current required by the memory cell
 - In the Off state: very low leakage current (it limits max. size of array)
 - Compatibility with the process of the memory cell.
 - Small size.
 - Scalability.
- ▶ The requirements are especially critical for memories that require bipolar switching.



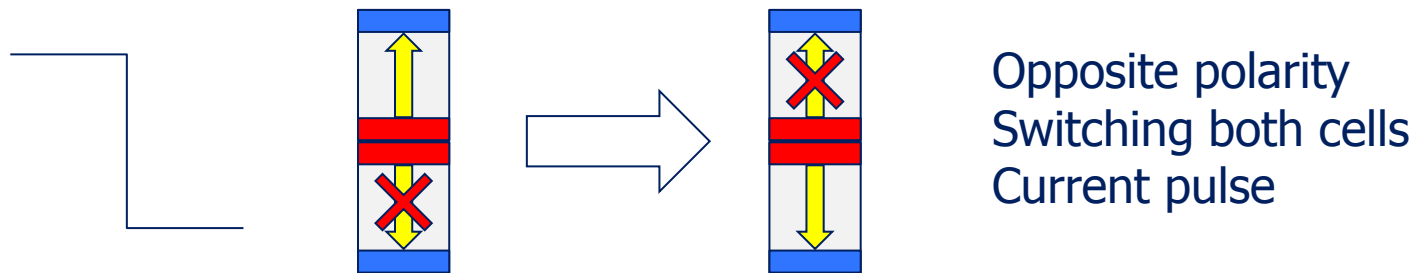
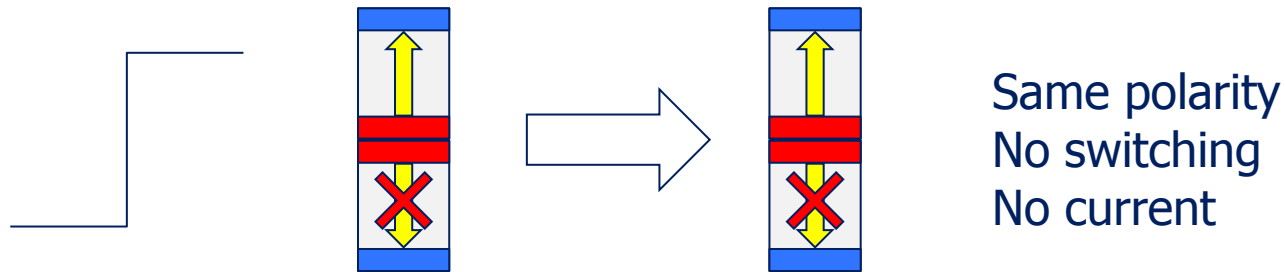
Selector types

- ▶ Transistor
 - MOS: easy to integrate, good performances, large size (DRAM, MRAM, FERAM)
 - Bipolar: more complex process, good performances, smaller size (PCM)
- ▶ Diodes (unipolar)
 - p-n in substrate: good performances, not for cross-point arrays
 - p-n in poly: can be integrated in back-end, poor Ion/Ioff
 - Schottky: low Ion density, poor Ion/Ioff
- ▶ Bipolar devices
 - Devices with strongly non-linear symmetrical I_V characteristics, e.g.
 - Metal-Insulator Transition switch (MIT), e.g. Mott transition switch:
 - Threshold Switch, e.g. Ovonic Threshold Switch
 - Mixed electronic and ionic conduction (MIEC)
 - Very little data available

Complementary Resistive Switch

- ▶ An architectural solution

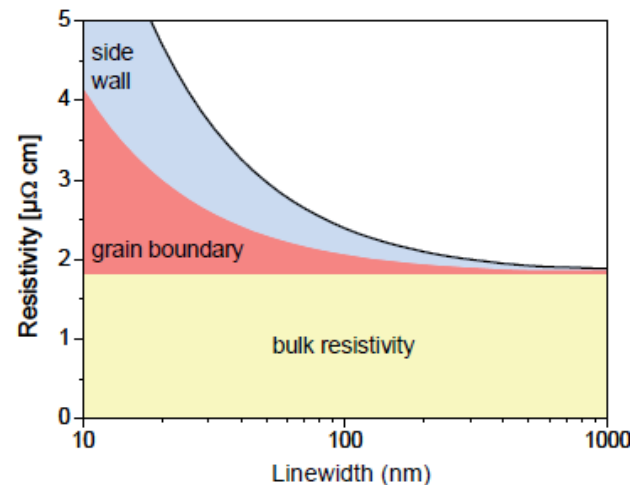
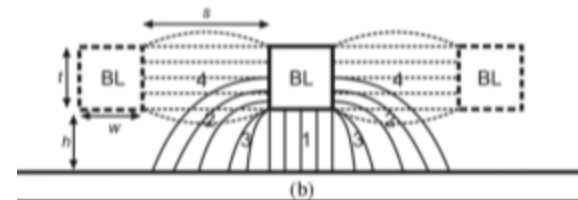
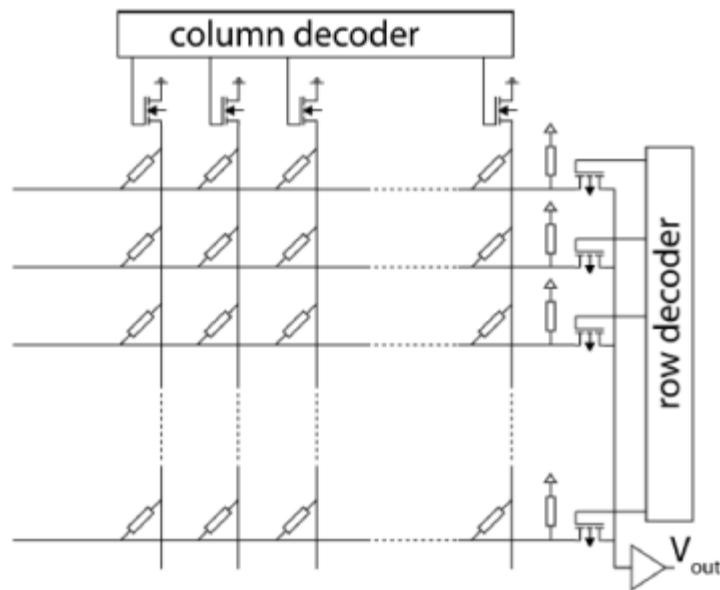
- Two bipolar RRAM disposed back-to-back.
- A voltage pulse generates a current pulse only if polarity is such as to switch both devices.



- Destructive reading as in FeRAM

Real Arrays

- ▶ In real arrays, parasitic capacitance and resistance of interconnects cannot be neglected.
- ▶ Uniform scaling keeps capacitance constant but increases resistance.

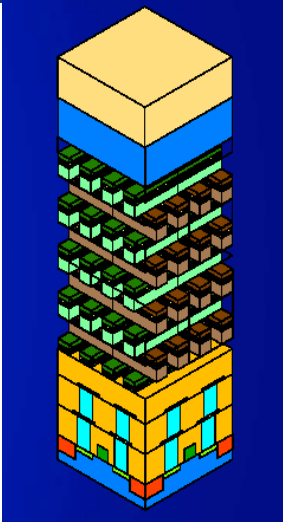


- ▶ Also resistivity increases because of sidewall scattering.
- ▶ Interconnection delay and capacitance charging time can limit size of memory arrays.

Outline

- ❑ Solid State Memories: a success story
- ❑ A lot of alternatives:
 - Prototypal memories
 - New concepts
- ❑ From cell to memory
- ❑ Is there a winner?

In summary



Source S.Lai

The ideal memory:

- ▶ High density
- ▶ Low power consumption
- ▶ Non-volatility
- ▶ Fast read/write/erase
- ▶ Random read/write access
- ▶ Endurance against write/erase cycles
- ▶ Scalability with low cost

and what is available (from ITRS ERD 2011)

Parameter	Prototypical (Table ERD3)			Emerging (Table ERD5)					
	FeRAM	STT-MRAM	PCRAM	Emerging ferroelectric	Nanomechanical memory	Redox memory	Mott Memory	Macromolecular memory	Molecular Memory
Scalability	☹	😊	😊	😊	☹	😊	?	?	😊
MLC	☹	☹	😊	☹	☹	😊	?	😊	☹
3D integration	☹	😊	😊	☹	☹	😊	?	😊	☹
Fabrication cost	😊	😊	😊	😊	☹	😊	?	😊	?
Endurance	😊	😊	😊	😊	☹	😊	😊	☹	?

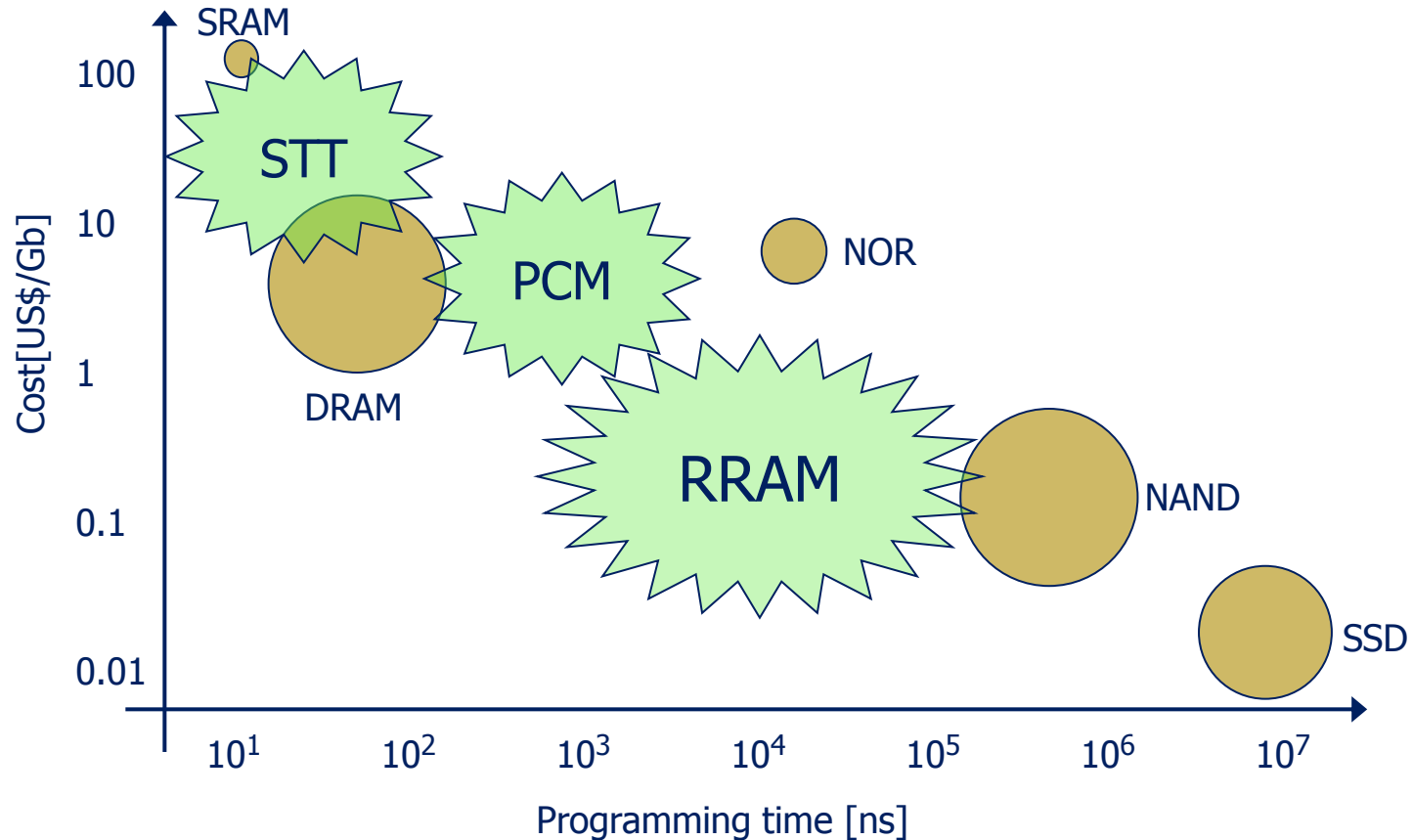
Probably we have to settle for less: no 'universal memory', but several new concepts with interesting performances.

Emerging Memories

A few warnings

- Most of the emerging memories have low programming voltages/energy:
 - Low power dissipation, high programming speed, but
 - Low temperature stability
 - Low reading voltage → low On/Off margin
 - Difficulty to have multilevel storage
 - High sensitivity to read disturbs
- Some concepts are not easily scalable (STT, FeRAM)
- Cross-point cell looks attractive, but:
 - Scaling depends on the availability of next generation lithography

The competition arena

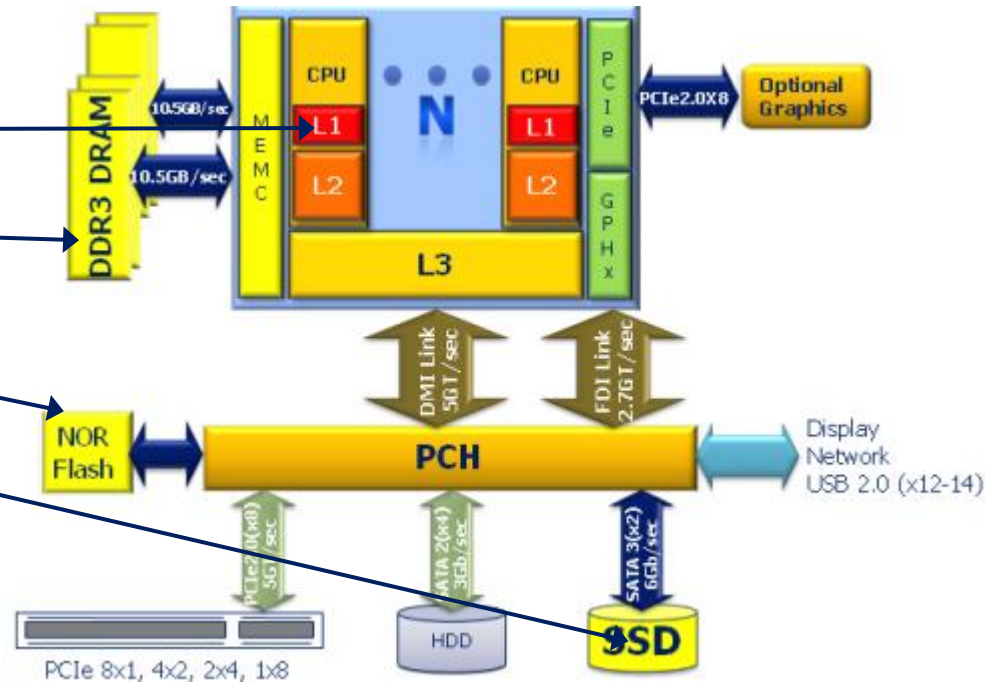


- ▶ New memories can fill the gaps between consolidated technologies
- ▶ Gain at system level.

Can we live with one memory?

Present PC architecture

- ▶ SRAM
- ▶ DRAM
- ▶ NOR Flash
- ▶ MLC NAND

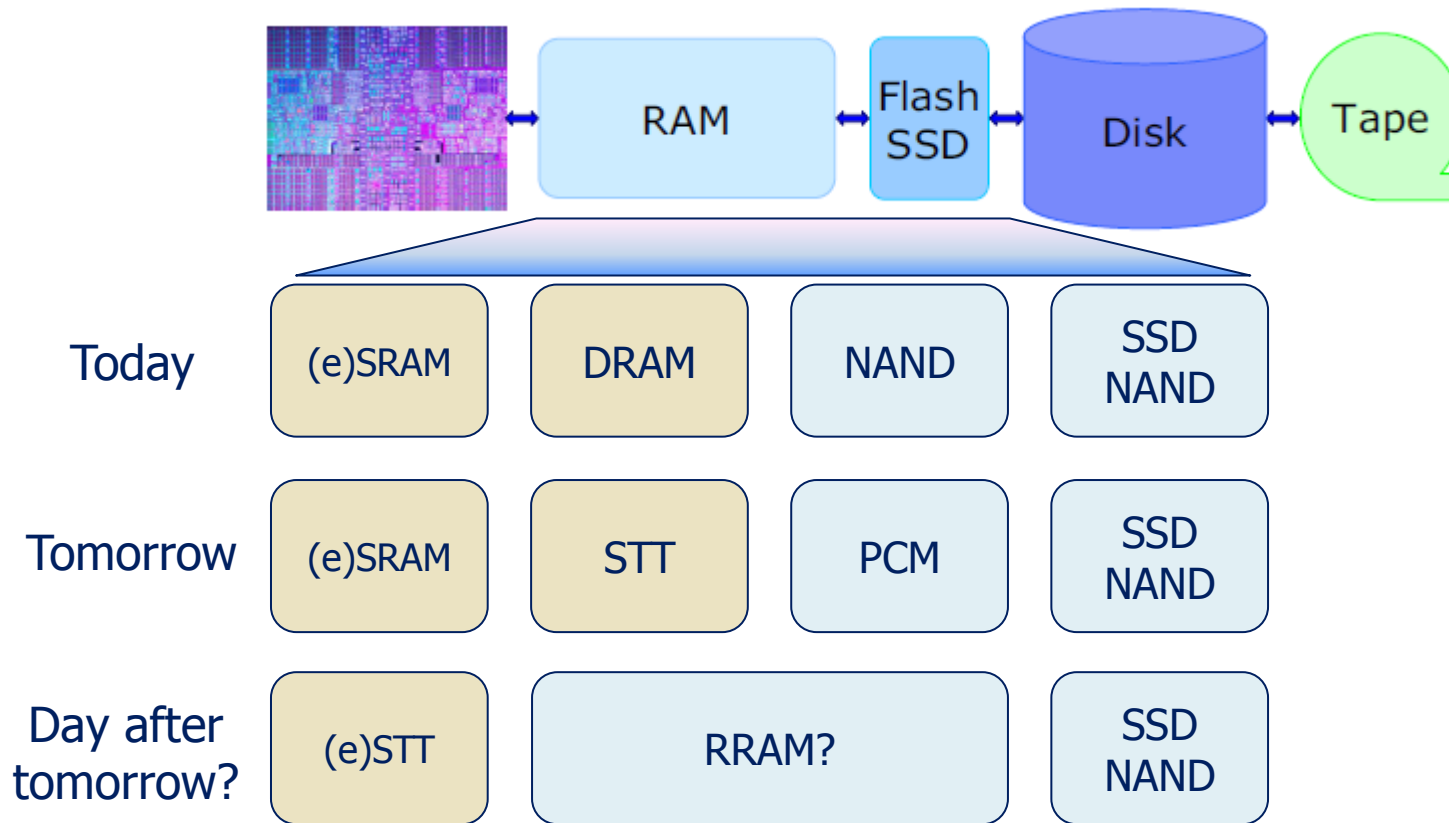


All types of available solid state memories are used.

Three strategy options for new memories:

- Compete with mainstream memory for cost (DRAM and NAND are hard to beat)
- Higher cost but replace more memory types (saving at system level)
- Find a niche in an intermediate position.

Computer architectures



A mixed future

- ▶ In the longer term the competition is still open between different alternative memories:
 - Choices on materials and architectures are needed to achieve critical mass.
 - Array and selector technology will be as important as the memory cell.
- ▶ Probably no “universal solution” but a differentiated landscape
- ▶ Memory systems combining different memory types in the same package will probably be the winning solution.